

# Research Grants for PhD students from the China Scholarship Council

Information Form (please read the guidelines carefully on the website [www-csc.utt.fr](http://www-csc.utt.fr))

Supervisor's name :  Given names :

Status (prof., assistant prof., ...) :

Laboratory :  Website address :

Institution :  Website address :

Scientific competence of the supervisor:

Expert in electronics and optoelectronics materials and devices based on SiC, GaN and related materials wide band gap– Solid state physics –Semiconductor and surface physics – Expert in optical ( PL, Raman, FTIR) and electrical ( I-V, C-V, admittance , capacitance, DLTS, DLOS) spectroscopies on semiconductor nanostructures, material and device characterization.

Two major publications in the field proposed for the PhD :

1.
2.

Website address of the personal page :

**Supervisor's email :**

**Description of the research work proposed for a PhD** **Topic # (see list) :**

Title :

Subject :

Gallium oxide (Ga<sub>2</sub>O<sub>3</sub>) under its monoclinic beta phase which is thermodynamically stable under ambient conditions, is a promising material for various applications in devices. Its transparency even to UV light due to its wide energy band gap of 4,9 eV gives prospective applications in UV applications, its high critical field of 8 MV/cm is promising for high voltage power applications and also in transparent contact when doped. Other advantages come from the availability of cheap bulk substrates, a large doping range for n-type and various existing epitaxy techniques ( PVD, MOCVD, MBE,...). There are however severe bottlenecks for its development: 1) low value of thermal conductivity of Ga<sub>2</sub>O<sub>3</sub> substrates, 2) difficulty to turn on of p-type doping, 3) high concentration of traps affecting the mobility, the carrier lifetime, the compensation of doping level and the voltage breakdown. The focus of this thesis is to investigate by extensive and complementary characterizations the nature of native and impurity related defect centers in n ( or p if available) type epi-layer grown on Si substrates in order to prevent disadvantage (1) by MOCVD ( coll. GEMAC laboratory from Versailles university). The principal techniques we apply are admittance, deep level transient and optical spectroscopy (DLTS-DLOS) to access respectively to shallow and deep levels traps within the whole wide bandgap.

Keywords :

Expected collaborations :

Background required from the applicant :

Existence of a PDF file detailing the proposal ("yes" or "no") :

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